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(54) SOLVENT-FREE PROCESS FOR THE PREPARATION OF PYRROLO (3,4C) PYRROLE COMPOUNDS

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Declaration under Rule 4.17

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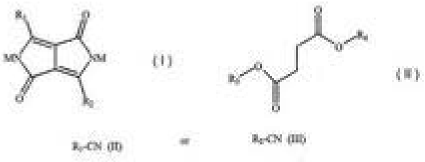

-- *with international search report*

(57) The invention relates to a *novel essentially-solvent-free process* for the preparation of 1,4-diketopyrrolo-[3,4-c]pyrrole compounds of general formula (I) in which both M represent hydrogen or an alkali metal, both R1 and R2 represent independently of the other an isocyclic or a heterocyclic aromatic radical, which process is characterized by reacting 1 mole of a disuccinate II wherein each R3 and R4 independently of the other is an alkyl or a cycloalkyl or an aryl radical, with 2 moles of a nitrile of the formula R1-CN (III) or R2-CN (IV) or a 2 mole mixture of the nitrile of formula (III) and the nitrile of the formula (IV),*essentially in the absence of any organic solvent* and in the presence of a strong base at elevated temperature, and obtaining the compound of formula (I) from the reaction product by subsequent hydrolysis when M represents hydrogen. Formulae (I, II). R1-CN (II) or R2-CN (III).